(19) World Intellectual Property Organization International Bureau



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(43) International Publication Date 28 April 2005 (28.04.2005)

PCT

(10) International Publication Number WO 2005/038834 A1

(51) International Patent Classification?:

H01G 9/025

(21) International Application Number:

PCT/JP2004/015762

(22) International Filing Date: 19 October 2004 (19.10.2004)

(25) Filing Language:

English

(26) Publication Language:

English

(30) Priority Data:

4

2003-359086 60/513.590 20 October 2003 (20.10.2003) JP 24 October 2003 (24.10.2003) US

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(84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Published:

with international search report

For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

(54) Title: PRODUCTION METHOD OF A CAPACITOR

(57) Abstract: A method for producing a capacitor having a good capacitance appearance factor and a low ESR comprising, as one electrode (anode), an electric conductor having pores and having formed on the surface thereof a dielectric layer and, as the other electrode (cathode), a semiconductor layer formed on the electric conductor by energization in an electrolytic solution, the method comprising impregnating pores with a semiconductor layer-forming precursor before energization to render the concentration of semiconductor layer-forming precursor in pores higher than that of semiconductor layer-forming precursor in the electrolytic solution; a capacitor produced by the method; and an electronic circuit and an electronic device using the capacitor.